

ABSTRACT

A blank mask including a transparent substrate and a light shielding film disposed on the transparent substrate, wherein the light shielding film comprises a transition metal and at least one selected from the group consisting of oxygen and nitrogen, and wherein when an optical density of the light shielding film is measured ten times by a light with a wavelength of 193 nm, a standard deviation of measured optical density is 0.009 or less, is disclosed.

FIG. 1